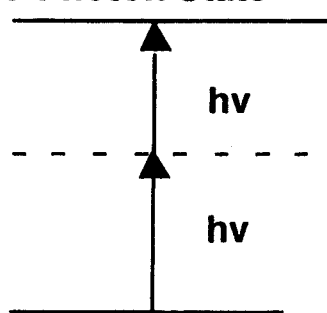


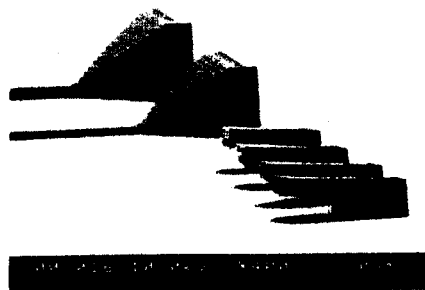
Two-Photon Absorbing Materials

Impact a Wide Range of Applications

Two-Photon State



Ground State

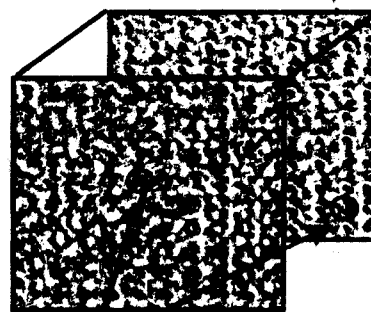


3-D Microfabrication

- Photonic Bandgap Materials
- Micro-optical Components
- MEMS

Two-Photon Induced Processes

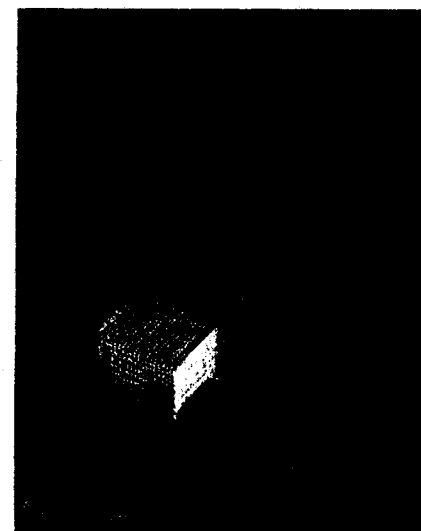
Light Emission
Photochemistry
Energy Transfer
Charge Transfer



"0" bits

3-D Optical Memory

- Terabit Storage
- 3D ROM
- Fluorescent Memory

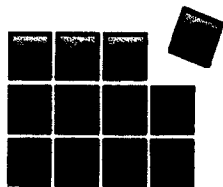


Biomedical Applications

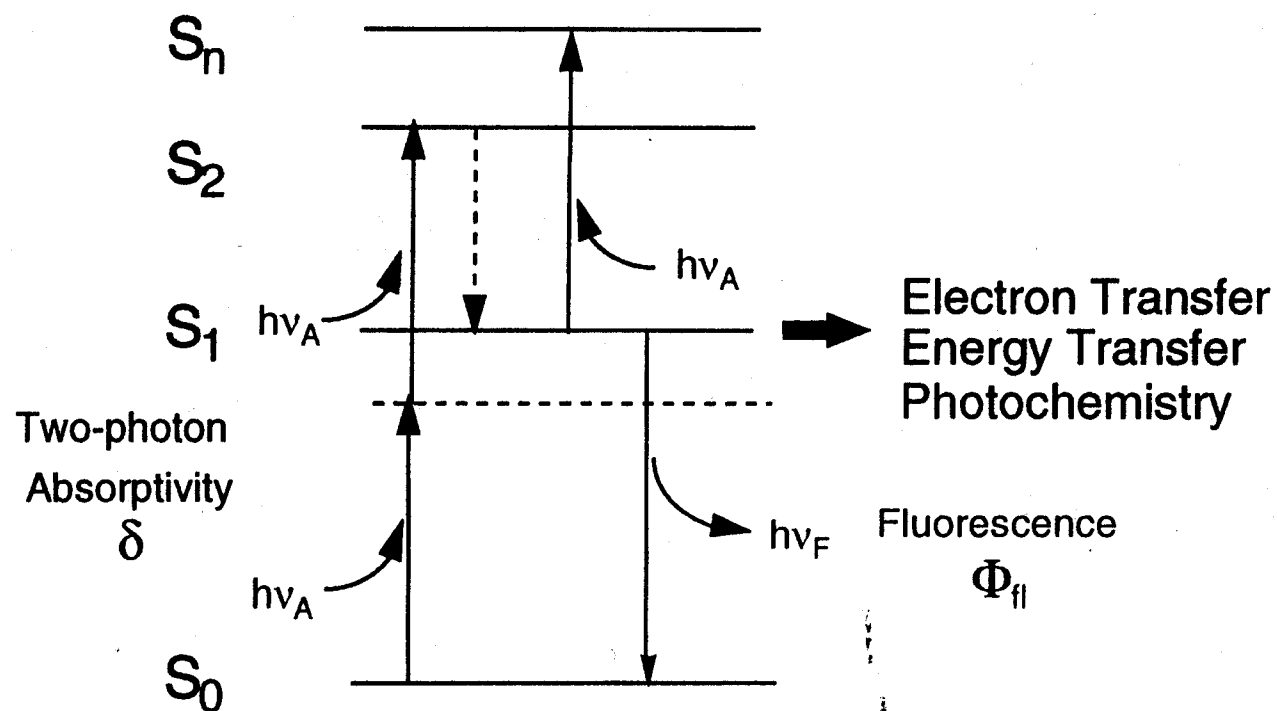
- Imaging in Tissues
- Photodynamic Therapy
- Immunological Assays

Outline

- **Two-photon absorption background**
- **Molecular design strategy**
- **Two-photon polymerization**
- **3D microstructures**
- **Two-photon patterning of metals**
- **Biological imaging**



Two-Photon Excited Processes



History of Two Photon Absorption

1931 — Two-photon absorption predicted by Maria Göppert-Mayer
Ann. Phys. 9, 273-295 (1931).

1960 — Invention of Laser

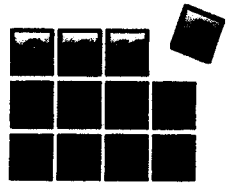
1961 — Two photon absorption is observed in $\text{CaF}_2:\text{Eu}^{+2}$ crystal
W. Kaiser and C.G.B. Garrett. Phys. Rev. Lett. 7, 229-231(1961).

1975 — Two-photon used as molecular spectroscopic tool

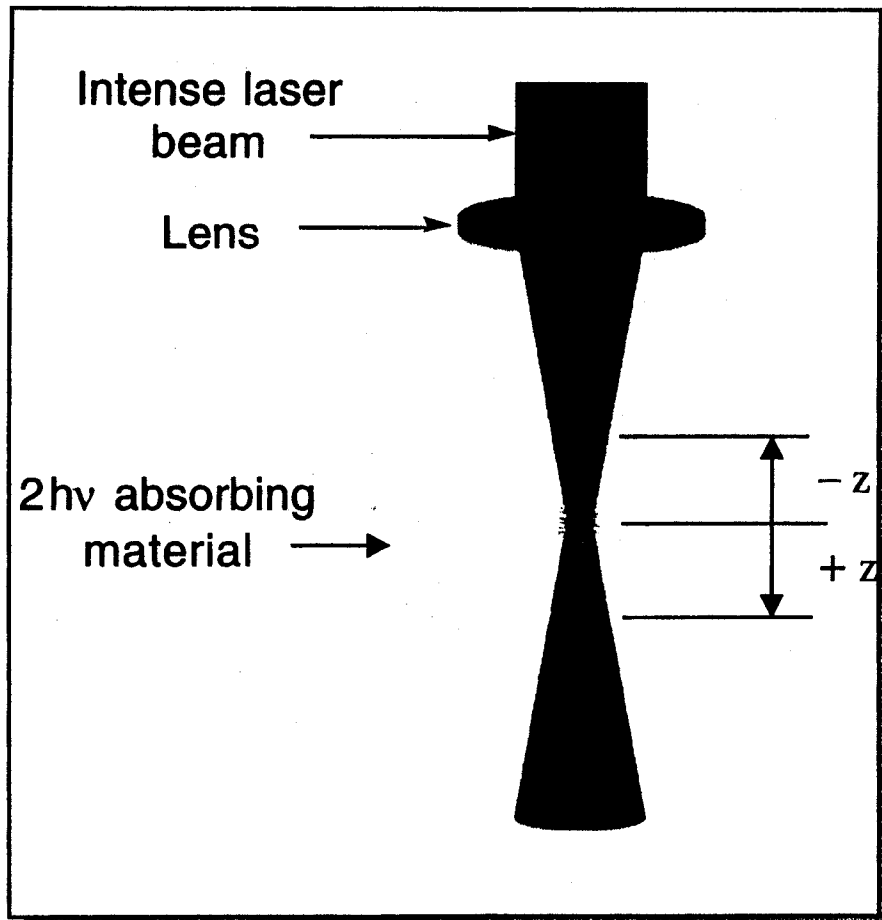
1990 — Two Photon Fluorescence Microscopy and Optical Data Storage

W. Denk, J.H. Strickler, W.W. Webb, Science (1990).

P. Rentzepis et al Science (1990)



Two-Photon Absorption: 3D Resolved Pinpoint Excitation



● 3-D Confinement

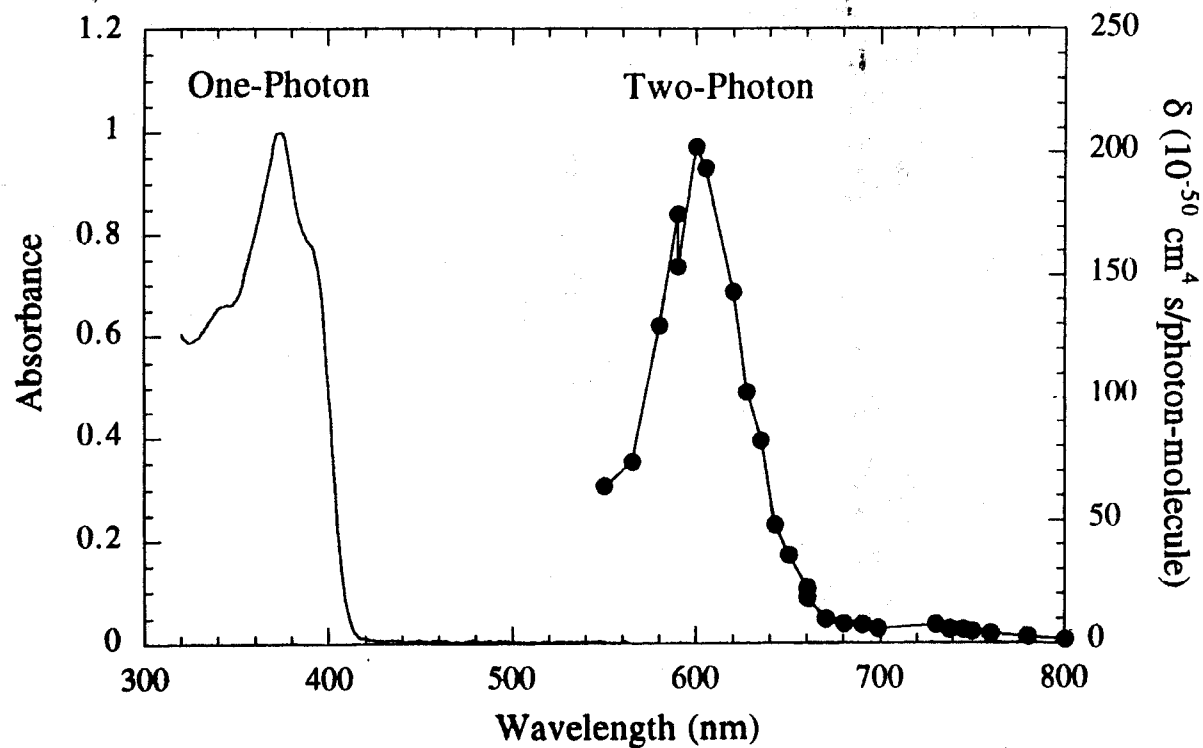
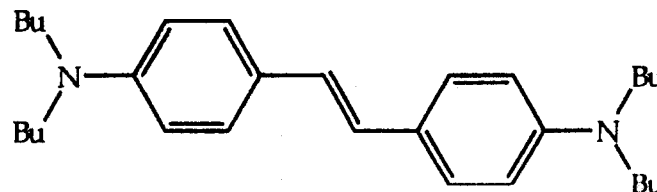
$$\text{TPA} \propto I^2$$

$$I \propto z^{-2}$$

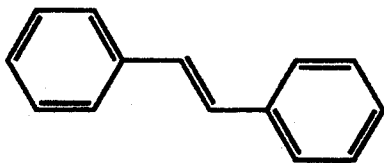
$$\text{TPA} \propto z^{-4}$$

Excitation at $\sim 2\lambda_{\text{op}}$ affords reduced linear absorption and scattering

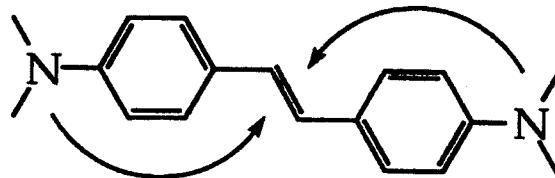
One- and Two-Photon Absorption Spectra for *Bis*(dibutylamino)stilbene (BDAS)



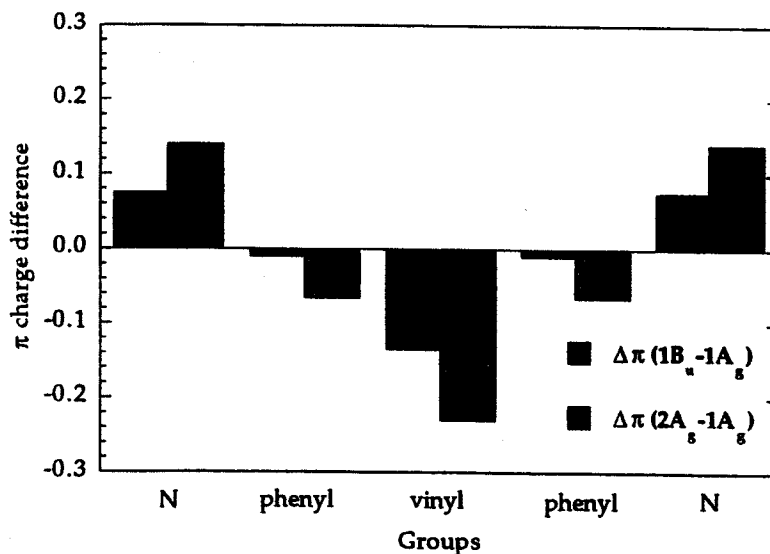
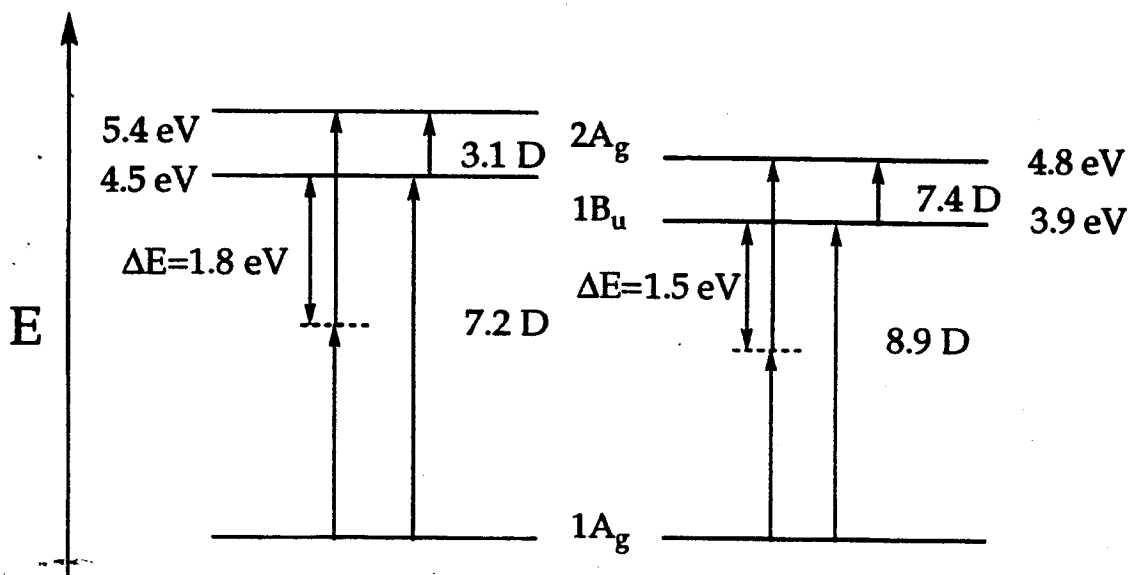
Effect of bis-Donor Substitution



$$\delta \approx 10 \times 10^{-50} \text{ cm}^4 \text{ s photon}^{-1}$$



$$\delta \approx 200 \times 10^{-50} \text{ cm}^4 \text{ s photon}^{-1}$$

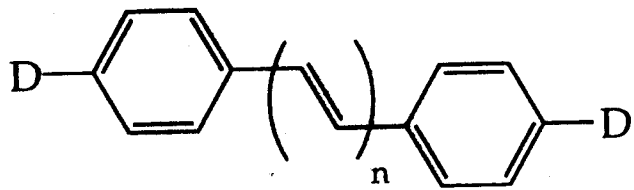


Semiempirical Calculations (Brédas et al. 1997)

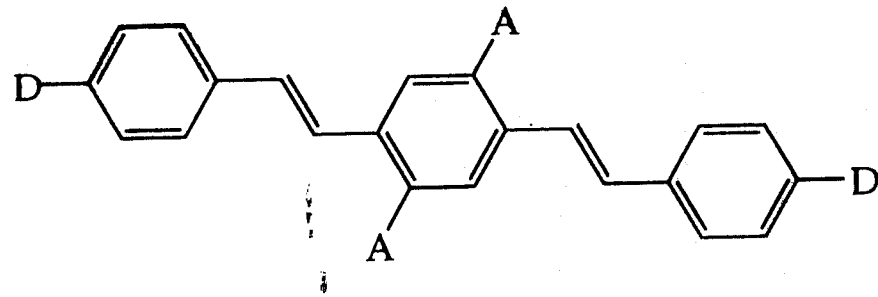
Strategies for the Design of New Materials

D- π -D

Increase conjugation length

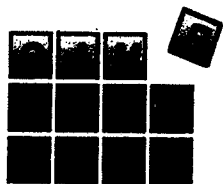


Add electron acceptors to the backbone

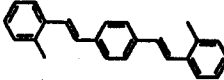
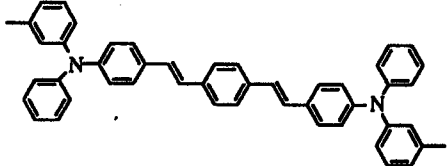
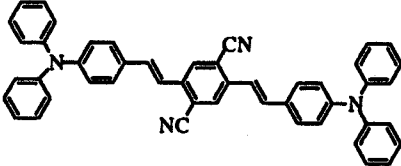
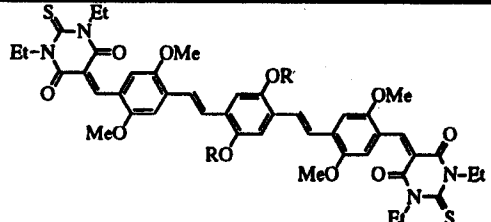
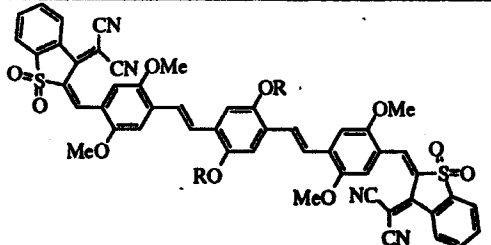


D- π -A- π -D

Also: A- π -D- π -A

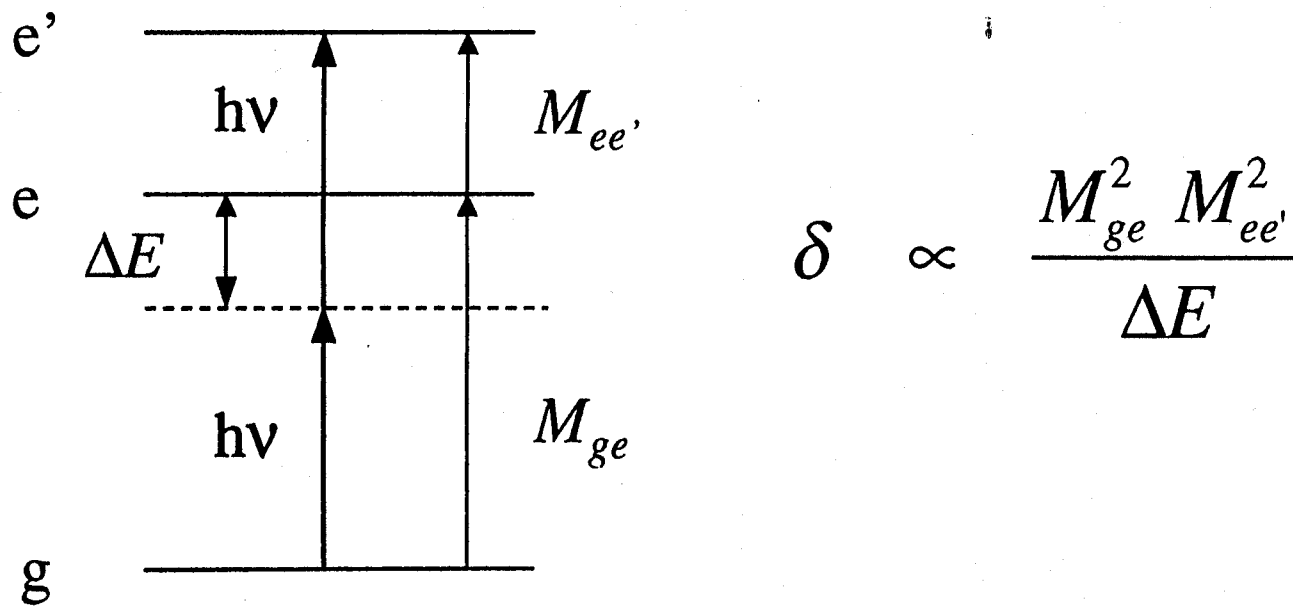


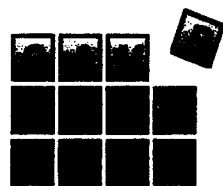
D-A-D and A-D-A Molecules

Compound	$\lambda_{\max}^{(2)}$ (nm)	δ_{\max} (GM)	Φ_{fl}
	568	55	0.95
	745	805	0.93
	835	1940	0.86
	970	1750	0.06
	975	4400	0.0085

● ~ 100 times
increase in δ

Two-Photon Absorption





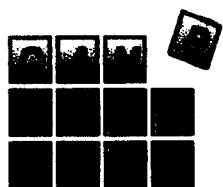
Effect of D/A Substitution

$$\delta_{ge'} \propto M_{ge}^2 M_{ee'}^2 \Delta E^{-2}$$

Compound	δ (GM)	ΔE (eV)	M_{ge} (D)	$M_{ee'}$ (D)
	55	1.41	8.9	2.9
	995	1.34	10.8	12.0
	1940	1.16	11.1	16.2
	1750	0.96	13.5	12.1
	4400	0.73	11.6	17.1

● Increase
in $M_{ee'}$

● Decrease
in $\Delta E =$
 $E_{ge} - \hbar\omega$



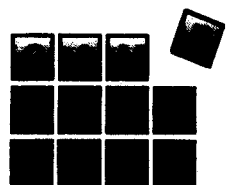
Effect of Increased Chain Length

$$\delta_{ge} \propto M_{ge}^2 M_{ee}^2 \Delta E^2$$

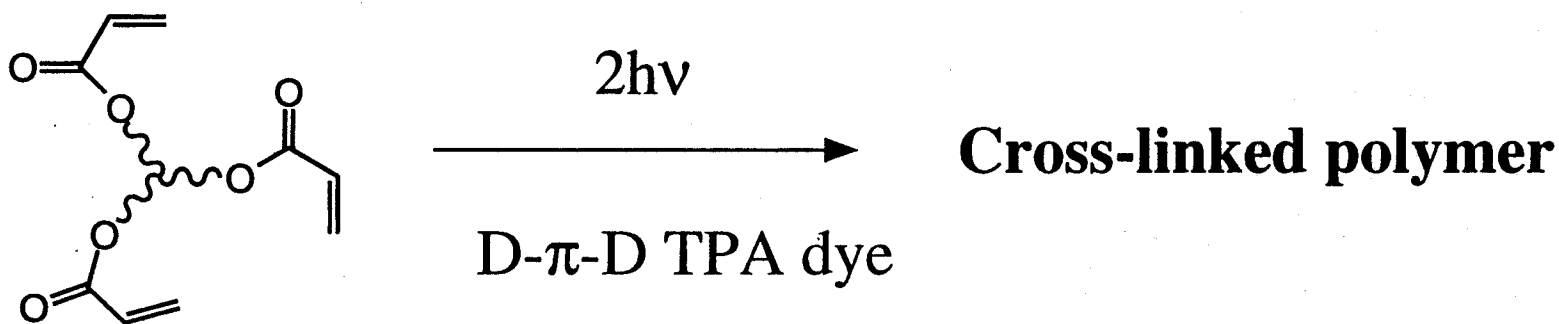
Compound	δ (GM)	ΔE (eV)	M_{ge} (D)	M_{ee} (D)
	210	1.26	7.7	6.0
	360	1.16	12.44	5.3
	995	1.34	10.8	12.0
	1250	1.14	11.9	10.9
	1420	1.17	14.5	10.7

● Increase
in M_{ge}

● Decrease
in $\Delta E =$
 $E_{ge} - \hbar\omega$

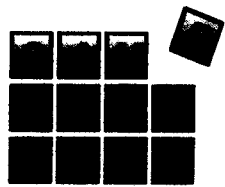


Two-Photon Photopolymer Systems



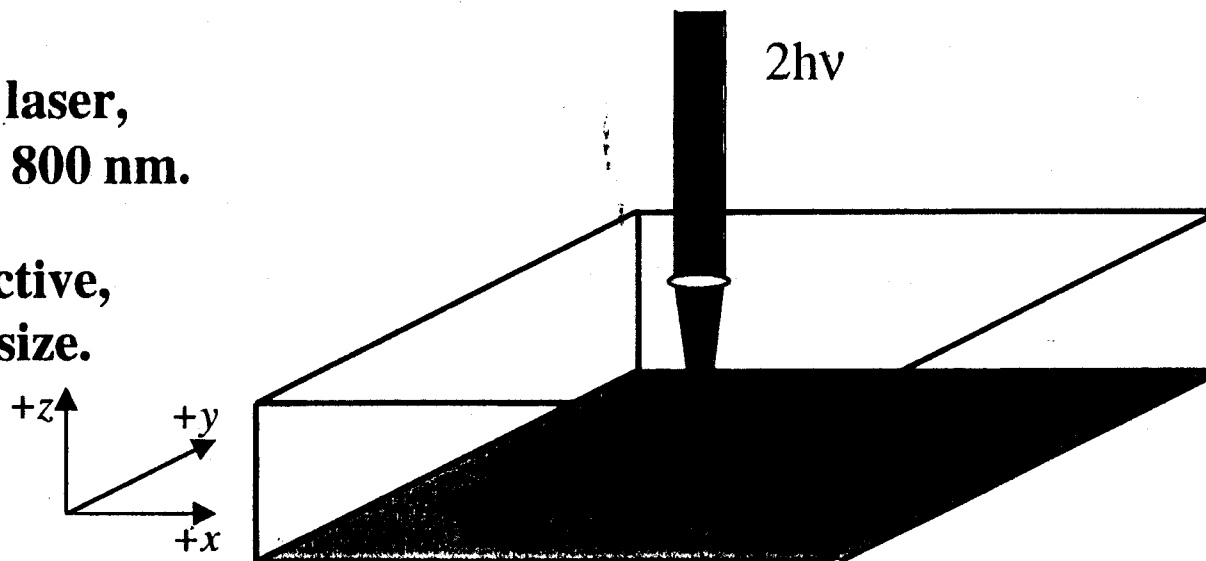
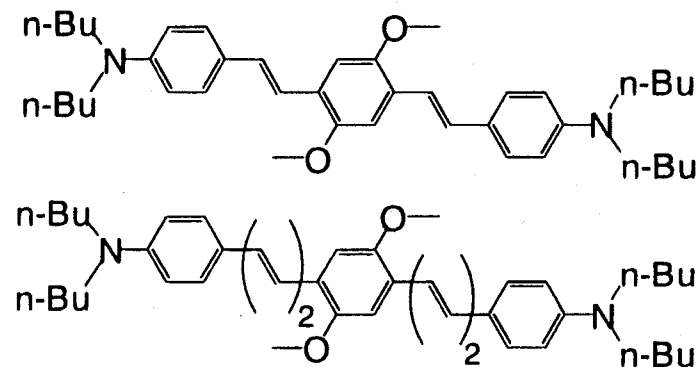
- Polymerization of triacrylates in liquids and solid photopolymer films
- Polymerization takes place in methanol--radical mechanism

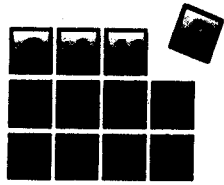
Two-photon cross-linking of acrylates forms the basis of our current photopolymer systems



3D Microfabrication in Two-Photon Photopolymer Films

- **Photopolymer: 70% crosslinkable acrylate monomer, 30% polymer binder, 0.1% two-photon initiator. Cast as 100-140 μm thick film.**
- **Laser: Ti:Sapphire laser, 150 fs pulses, 730 or 800 nm.**
- **Optics: 1.4 NA objective, 0.35 μm radial spot size.**



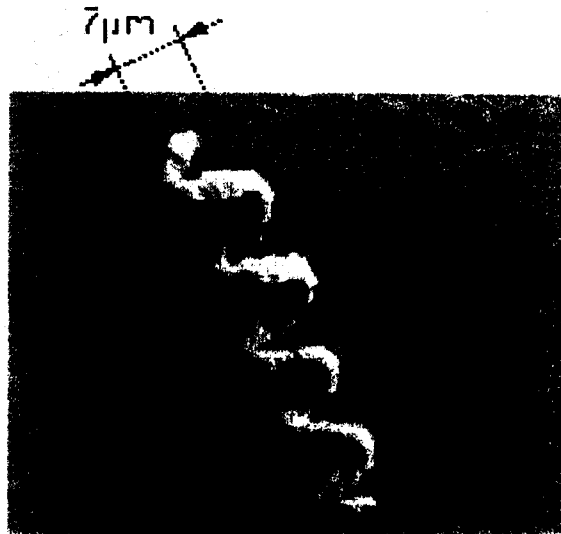


Two-Photon 3D Micro-fabrication ca. 1995



Strickler & Webb SPIE 1398, 107
(1990)

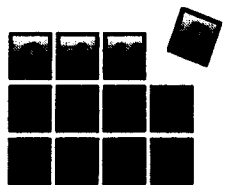
Writing conditions:
100 fs pulses, 5 mW, 10 ms dwell time
(0.2 ms threshold)



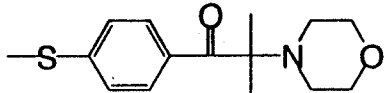
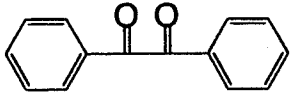
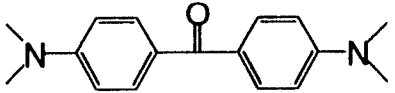
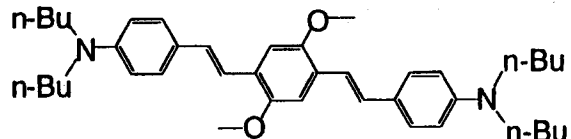
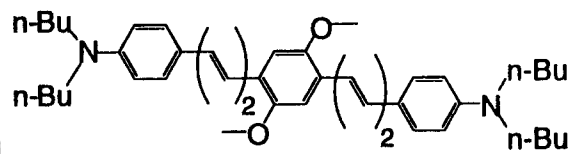
Maruo & Kawata Opt. Lett. 22,
132 (1997)

Writing conditions:
200 fs pulses, 20 mW, 8 ms dwell
time

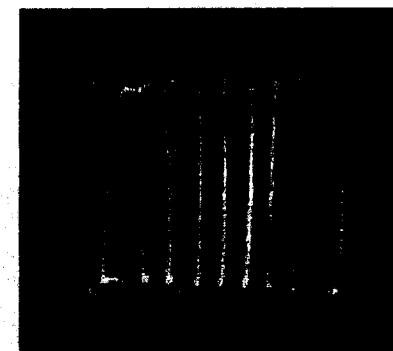
**Early work employed commercially available UV photoinitiators
which have small two-photon absorptivities**



New Dyes Provide Improved Sensitivity for Two-Photon Polymerization

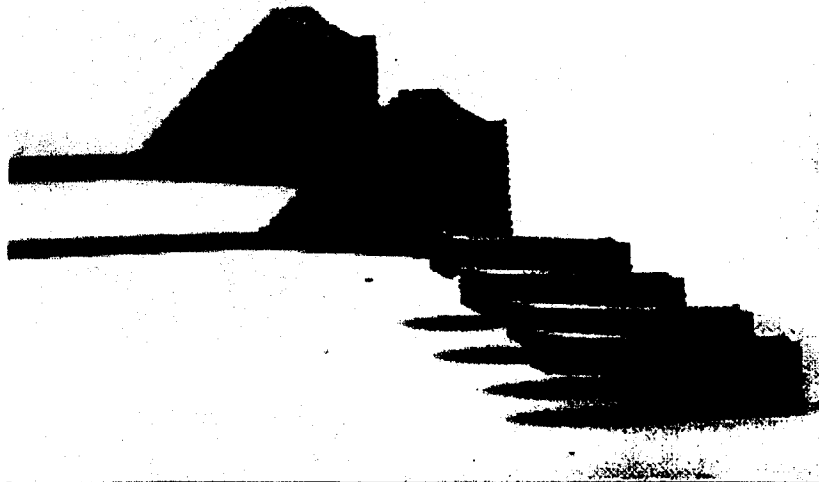
Initiator	Writing Threshold (mW)	Writing Power range
	~10	1
	~10	1
	4	2.5
	0.2	50
	0.3 (800 nm)	33

New
Dyes

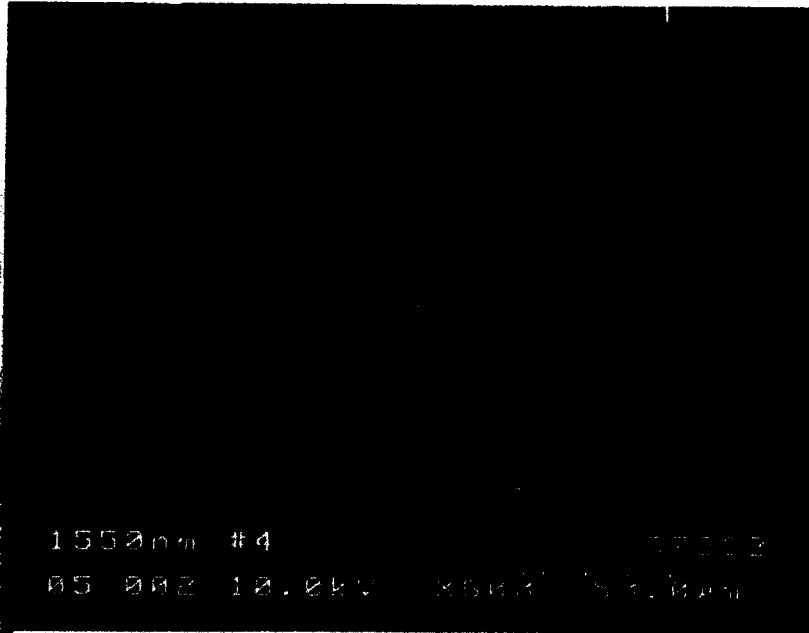


Data for 120 fs Pulses at 730 nm, 20 ms dwell time

Micro-Optics and MEMS by Two-Photon Polymerization

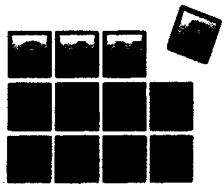


00 016 10.0kV X400 75.0µm



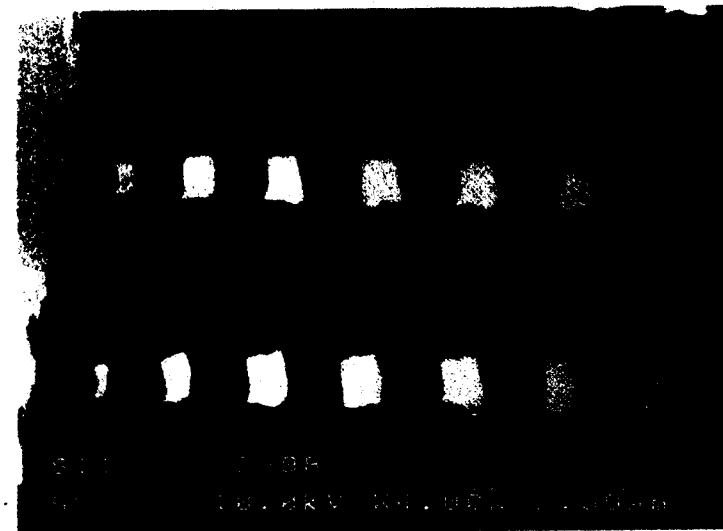
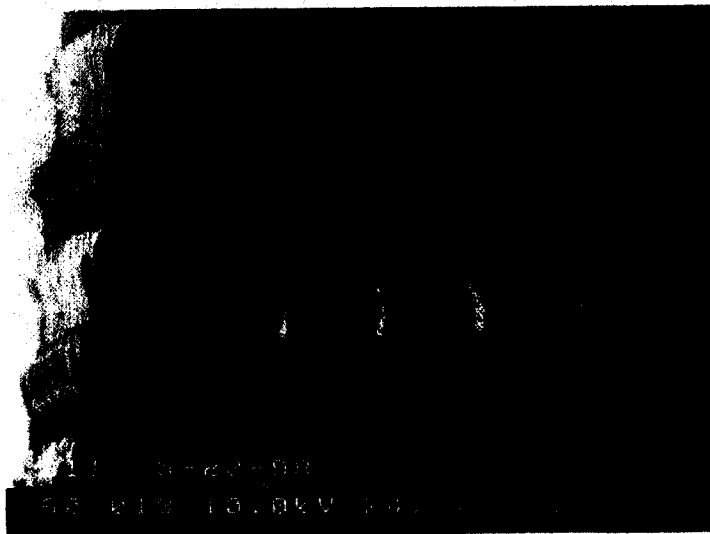
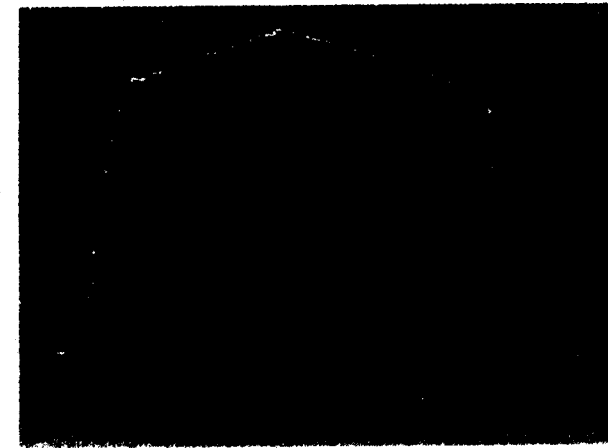
1550nm #4 17002
05 002 10.0kV X500 75.0µm

*Two-photon photopolymers provide capability to
fabricate complex 3D microstructures*



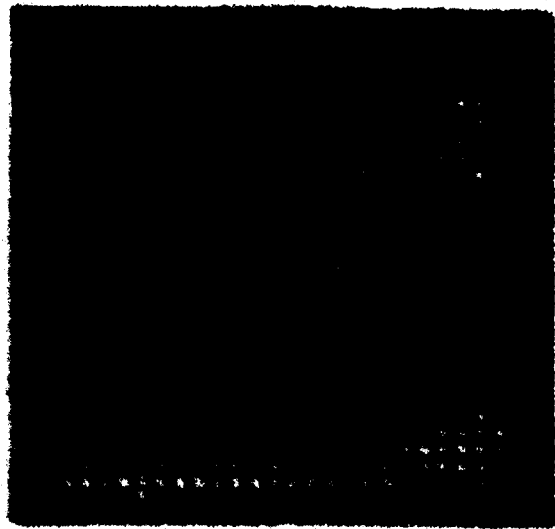
Photonic Bandgap Structures

- 3D periodic structures -- Infrared filters, waveguides, & camouflage.
- “Stack-of-logs” with 5 μm periodicity; useful in the IR; fabricated in a single step.
- Structure can be coated or filled for higher dielectric contrast.



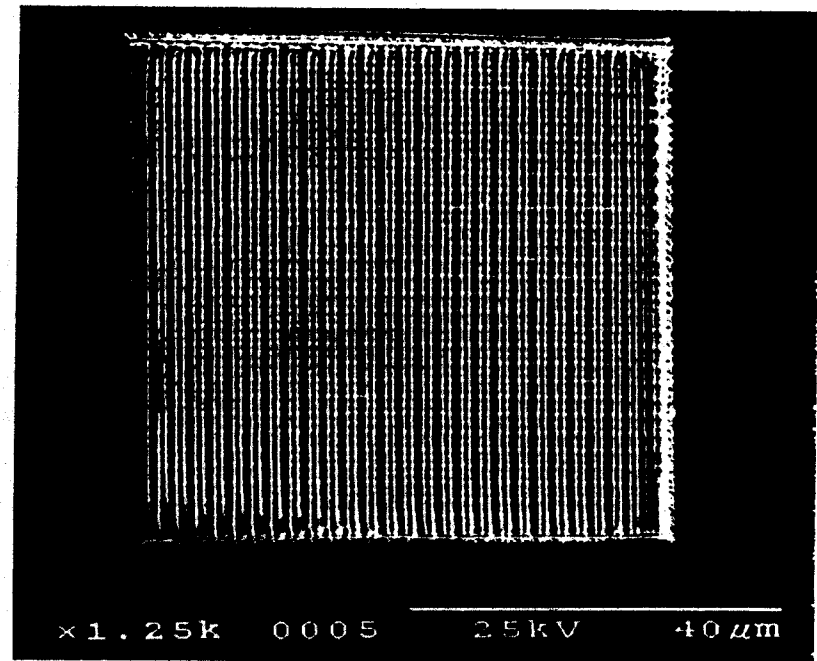
Photonic Bandgap Structure

~1 μm period



60 μm

Optical microscope image

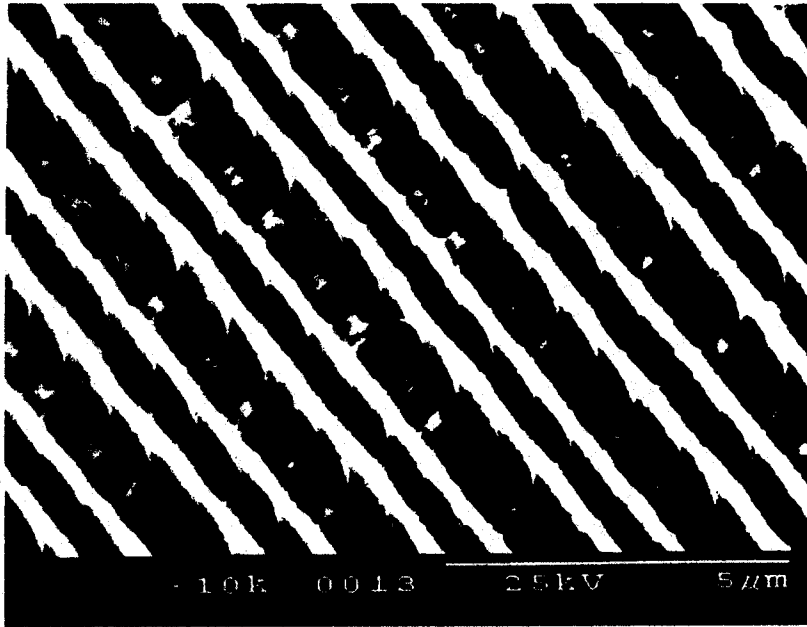


x1.25k 0005 25kV 40 μm

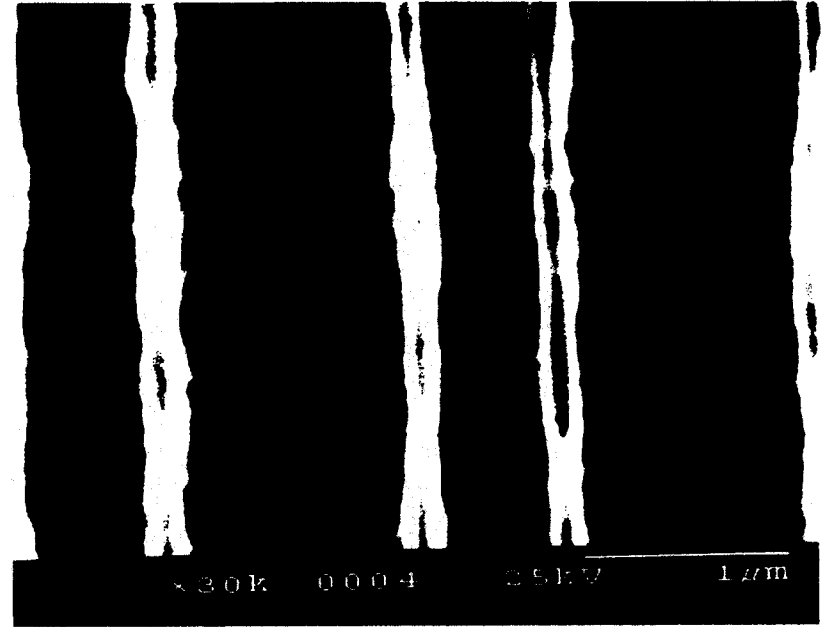
Scanning electron
micrograph

Photonic Bandgap Structure

~1 μm period

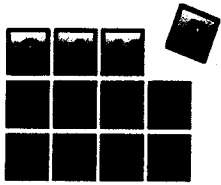


Scanning electron
micrograph



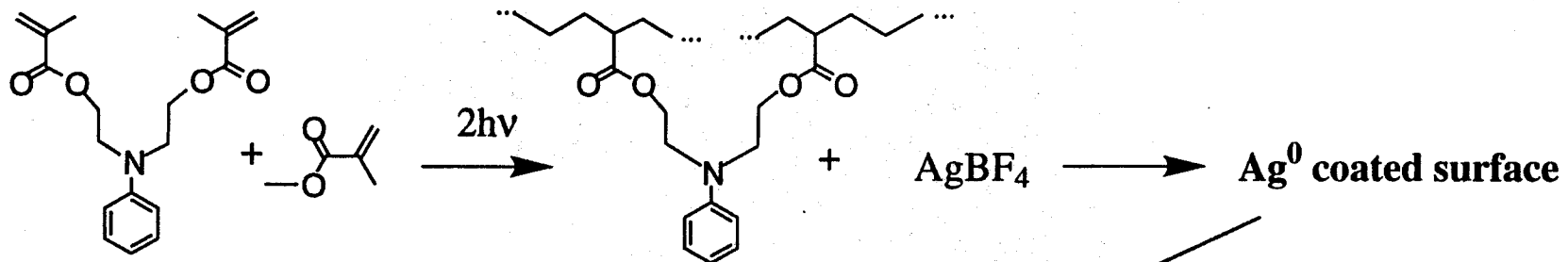
Scanning electron
micrograph.

~200 nm linewidth

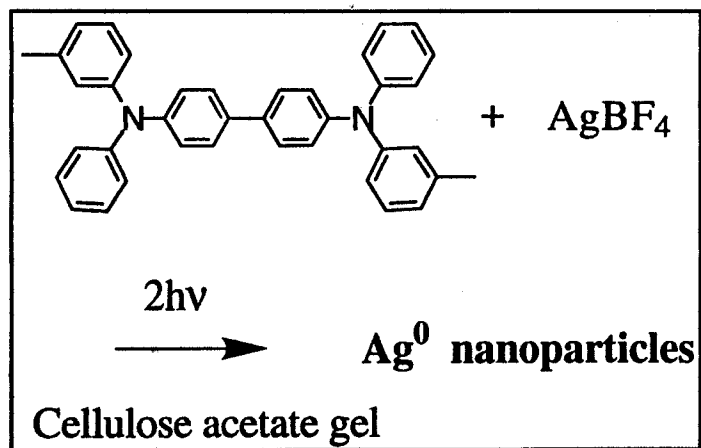


Methods for Two-Photon Photodeposition of Ag Metal

Method 1

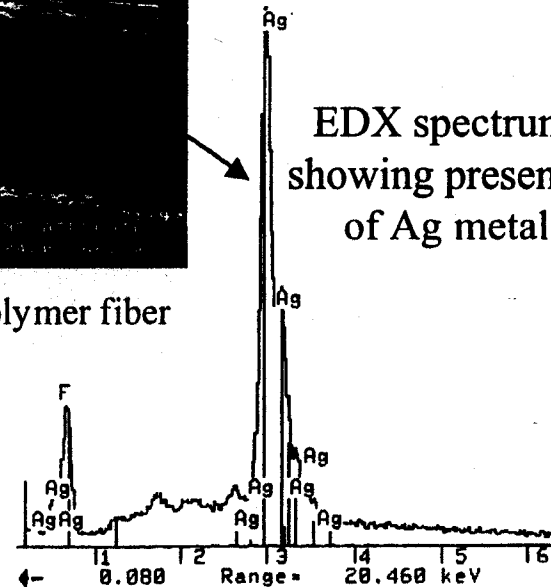


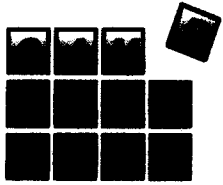
Method 2



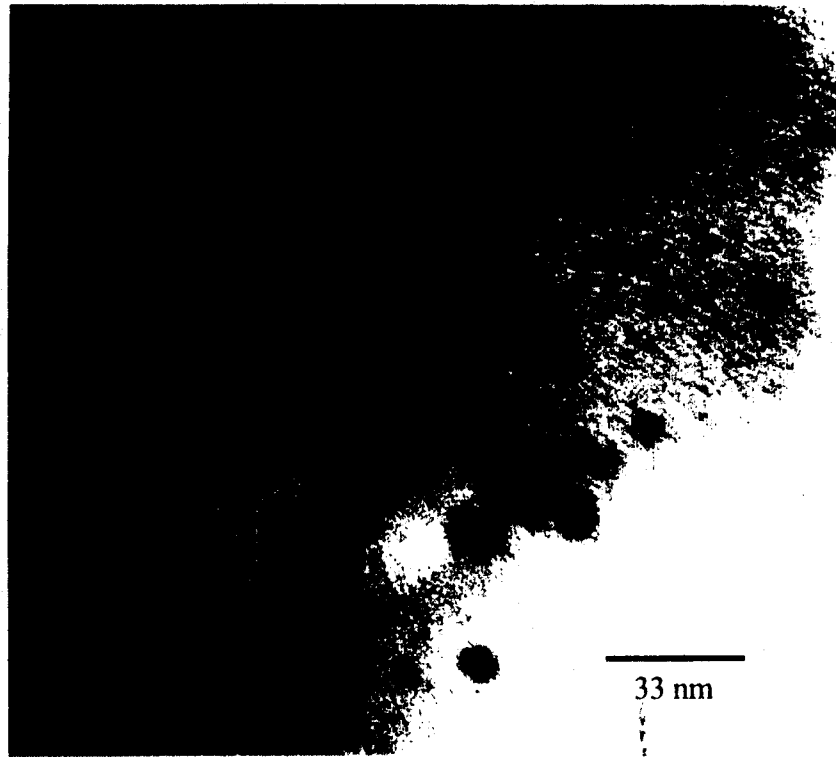
Ag coated polymer fiber

EDX spectrum
showing presence
of Ag metal





Photochemically Produced Ag Nanoparticles



TEM Image